

ISPlasma is an annual international symposium which aims to establish scientific research foundation of advanced plasma nanotechnology with global competitiveness in Tokai region as part of the Tokai Region Nanotechnology Manufacturing Cluster supported by MEXT.

## RELATED FIELD

### PLASMA SCIENCE

|                              |                                      |
|------------------------------|--------------------------------------|
| Plasma Source                | Advanced Plasma Measuring Technology |
| Modeling and Simulation      | Etching Process                      |
| Thin Film Deposition Process | Flexible Electronics                 |
| Plasma Biology and Medicine  | Plasma for Clean Energy              |
| Plasma for Nanotechnology    |                                      |

### NITRIDE SEMICONDUCTORS

|   |                        |
|---|------------------------|
| Crystal Growth of GaN and Related Materials | MBE Growth of Nitrides |
| Characterization                            | Device Processing      |
| Optical Devices                             | Electronic Devices     |

### NANOMATERIALS

|   |   |
|---|---|
| Nanocarbon Materials                            | Porous Materials                        |
| Surface Modification/ Surface Functionalization | Composite/ Functionally Grade Materials |
| Nanoparticle/Nanowire/Nanorod                   | Nanomaterials for Energy Applications   |

## AWARD

Mar. 8 (Thu), 17:45~  
Miura Kohei Memorial Hall, Chubu University  
"ISPlasma2012 Awards" will be given to outstanding papers.

## SPECIAL ISSUE

- Selected papers will be published in a special issue of JPN. J. Appl. Phys. (JJAP)
- Submission Deadline: **Mar. 30 (Fri), 2012**

## EXHIBITION

- During the symposium, enterprises and related organizations will exhibit at the venue.
- Date: Mar. 5 (Mon) to Mar. 8 (Thu)

## SOCIAL EVENT

- |  |   |
|--|---|
| <b>Welcome Party</b><br>Mar. 4 (Sun), 18:00~<br>Student Cafeteria III,<br>Chubu University | <b>Banquet</b><br>Mar. 6 (Tue), 18:30~<br>Student Cafeteria I, Chubu University<br>Fee: General 5,000 JPY/Student 2,000 JPY |
|--|---|

## RELATED CONFERENCES

- The 5th International Conference on PLASMA-Nano Technology & Science (IC-PLANTS 2012)  
Mar. 9-10, 2012  
Freude, Inuyama, Japan

## REGISTRATION

Please register on our website.

| Registration Fee :                  | General          | Student          |
|-------------------------------------|------------------|------------------|
| Early Registration (before Jan. 31) | JPY 20,000       | JPY 3,000        |
| Late Registration (until Feb. 23)   | JPY 25,000       | JPY 5,000        |
| On-site Registration                | JPY 30,000       | JPY 7,000        |
| <b>Banquet Fee (on Mar. 6)</b>      | <b>JPY 5,000</b> | <b>JPY 2,000</b> |

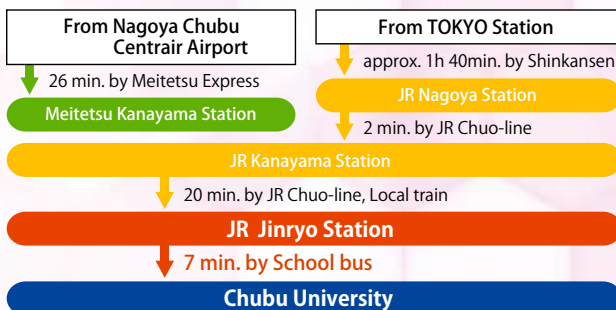
**Attendees of the March 6, PM Session ONLY: FREE of charge.**  
(Industry-Academia-Government Collaboration Lecture and Panel Discussion)  
\* **Advanced online registration is required.**

## SCHEDULE AT A GLANCE

|                     |   |
|---------------------|---|
| <b>Mar. 4 (Sun)</b> | Tutorial Session<br>Welcome Party at Student Cafeteria III, Chubu University  |
| <b>Mar. 5 (Mon)</b> | Opening<br>Plenary Lecture: Atsuo Iiyoshi (Chancellor of Chubu University)<br>Technical Session<br>Poster Session   |
| <b>Mar. 6 (Tue)</b> | Technical Session<br>Poster Session<br>Panel Discussion<br>"Establishment of Global Research Hub toward Sustainable Development"<br>Banquet at Student Cafeteria I, Chubu University                                    |
| <b>Mar. 7 (Wed)</b> | Technical Session<br>Poster Session<br>Panel Discussion<br>"Application of Advanced Plasma Technology for Nitride Semiconductors III<br>-Importance and problem of plasma processing in nitride semiconductor devices-" |
| <b>Mar. 8 (Thu)</b> | Technical Session<br>Panel Discussion<br>"Advanced Plasma Nanotechnology towards Green Innovation"<br>Award<br>Closing  |

## VENUE

**Chubu University** | 1200, Matsumoto-cho, Kasugai-shi, Aichi, JAPAN  
Phone: +81-568-51-1111 (Representation)



\*There are extra school buses between Jinryo Station and Chubu University during ISPlasma 2012.  
Bus Fare: 200 JPY



**4th International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials**

**March 4-8, 2012**  
**Chubu University, Aichi, Japan**

## Organizing Committee

### Chairperson

**Masaru Hori**, Plasma Nanotechnology Research Center, Nagoya University

### Vice-Chairperson

**Hideki Masuda**, Nagoya Institute of Technology  
**Hiroshi Amano**, Nagoya University  
**Mineo Hiramatsu**, Meijo University

### Sponsored by :

**Aichi Science & Technology Foundation,**  
**ISPlasma2012 Organizing Committee**

### Co-sponsored by :

Aichi Prefecture, Nagoya City, Gifu Prefecture, Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, The Japan Society of Applied Physics, The Japan Society of Plasma Science and Nuclear Fusion Research, The Japanese Association for Crystal Growth

### Grants :

Support Center for Advanced Telecommunications Technology Research, Foundation, Foundation for Promotion of Material Science and Technology of Japan, Research Foundation for the Electrotechnology of Chubu

### Contact

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<http://www.isplasma.jp/>

# ISPlasma2012

MAR  
4  
SUN

## TUTORIAL SPEAKERS

### PLASMA SCIENCE

U. Czarnetzki (Ruhr-University Bochum, GERMANY)  
A. Kono (Nagoya University, JAPAN)

### NITRIDE SEMICONDUCTORS

H. Amano (Nagoya University, JAPAN)  
A. Khan (University of South Carolina, USA)

### NANOMATERIALS

J. G. Han (Sungkyunkwan University, KOREA)  
M. Hiramatsu (Meijo University, JAPAN)

MAR  
5  
MON

## PLENARY SPEAKER

Atsuo Iiyoshi (Chubu University, JAPAN)

## KEYNOTE SPEAKERS

### NITRIDE SEMICONDUCTORS

Y. Nanishi (Ritsumeikan Univ., JAPAN/Seoul National Univ., KOREA)  
T. Palacios (Massachusetts Institute of Technology, USA)

### NANOMATERIALS

P. Kamat (University of Notre Dame, USA)

### PLASMA ASSISTED GROWTH

**Focused Session**

J. Speck (University of California Santa Barbara, USA)

### ADVANCED CARBON MATERIALS

M. Meyyappan (NASA Ames Research Center, USA)

### ADVANCED NITRIDE DEVICES

B. Daudin (CEA-Grenoble, FRANCE)

### GREEN INNOVATION

R. Nemanich (Arizona State University, USA)

### INDUSTRY-ACADEMIA-GOVERNMENT COLLABORATION

T. Degawa (TECHNO INTEGRATION Co. Ltd, JAPAN)  
W. Izumiya (Sangyo Times, Inc., JAPAN)  
T. Koljonen (VTT Technical Research Centre of Finland, FINLAND)  
S. Ohmori (YRP International Alliance Institute, JAPAN)

## INVITED SPEAKERS

### PLASMA SCIENCE

R.P. Brinkmann (Ruhr-University Bochum, GERMANY)  
P. Favia (University of Bari, ITALY)  
M. Goeckner (University of Texas at Dallas, USA)  
A. Ito (National Institute for Fusion Science, JAPAN)  
T. Kaneko (Tohoku University, JAPAN)  
G. Oehrlein (University of Maryland, USA)  
H. Shea (EPFL, SWITZERLAND)

### NITRIDE SEMICONDUCTORS

K. Chen (The Hong Kong University of Science and Technology, CHINA)  
T. Hashimoto (SixPoint Materials, Inc., USA)  
K. Kishino (Sophia University, JAPAN)  
J. Suda (Kyoto University, JAPAN)

### NANOMATERIALS

Y. Awano (Keio University, JAPAN)  
H. Yamaguchi Greenslet (University of Florida, USA)  
S. Inagaki (Toyota Central R&D Labs., Inc., JAPAN)  
X. Li (Peking University, CHINA)  
P. Mayrhofer (Montanuniversitaet Leoben, AUSTRIA)  
H. Nishihara (Tohoku University, JAPAN)

### ADVANCED NITRIDE DEVICES

**Focused Session**

T. Hashizume (Hokkaido University, JAPAN)  
Y. Saito (Toshiba Corporation Semiconductor & Storage Products Company, JAPAN)

### ADVANCED CARBON MATERIALS

M. Hasegawa (AIST, JAPAN)

### GREEN INNOVATION

T. Nozaki (Tokyo Institute of Technology, JAPAN)  
V. Svrcek (AIST, JAPAN)  
A. Yoshikawa (Chiba University, JAPAN)

## PANEL DISCUSSION

March 6 **TUE**

### Establishment of Global Research Hub toward Sustainable Development

**Simultaneous Interpretation**

<Moderator> N. Odake (Nagoya Institute of Technology, JAPAN)

<Panelist>

T. Degawa (Techno Integration Co. Ltd, JAPAN)  
M. Hori (Nagoya University, JAPAN)  
W. Izumiya (Sangyo Times, Inc., JAPAN)  
T. Koljonen (VTT Technical Research Centre of Finland, FINLAND)  
S. Ohmori (YRP International Alliance Institute, JAPAN)

\* Attendees of this session ONLY: **free of charge.**

March 7 **WED**

### Application of Advanced Plasma Technology for Nitride Semiconductors III

**Focused Session**

*-Importance and problem of plasma processing in nitride semiconductor devices-*

<Moderator> H. Amano (Nagoya University, JAPAN)

<Panelist>

T. Hashizume (Hokkaido University, JAPAN)  
T. Kachi (Toyota Central R&D Labs., Inc., JAPAN)  
Y. Nanishi (Ritsumeikan Univ., JAPAN/Seoul National Univ., KOREA)  
Y. Saito (Toshiba Corporation Semiconductor & Storage Products Company, JAPAN)  
J. Suda (Kyoto University, JAPAN)

March 8 **THU**

### Advanced Plasma Nanotechnology towards Green Innovation

**Focused Session**

<Moderator> T. Nozaki (Tokyo Institute of Technology, JAPAN)

<Panelist>

M. Kambara (The University of Tokyo, JAPAN)  
K. Koumoto (Nagoya University, JAPAN)  
M. Meyyappan (NASA Ames Research Center, USA)  
R. Nemanich (Arizona State University, USA)  
V. Svrcek (AIST, JAPAN)

\* Program and speakers listed above may change.

\* Listed in alphabetical order.

\* For detailed program, please visit our website.